

SU-8 2002 – run sheet

Kayaku Advanced Materials

nanyte.com/photoresists/su-8-2002 · last updated 2026-09-13

Thickness: 2.0–2.9 μm

Softbake: 95 °C · hotplate

Exposure dose – dose by film thickness

Film thickness Dose

0.5–2 μm 60–180 mJ/cm^2

3–5 μm 90–105 mJ/cm^2

6–15 μm 110–140 mJ/cm^2

16–25 μm 140–150 mJ/cm^2

26–40 μm 150–160 mJ/cm^2

Post-exposure bake: 95 °C · hotplate

Develop: Developer SU-8 Developer; ethyl lactate or diacetone alcohol may also be used · Rinse Spray and wash the developed image with fresh SU-8 developer for about 10 s, then air-dry with filtered pressurised air or nitrogen. · Method immersion, spray or spray-puddle

Hardbake: 150–250 °C · 5–30 min